

FILE 'REGISTRY' ENTERED AT 13:54:55 ON 11 SEP 2002

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 11 S L3 FULL
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 8 S L7 FULL
L9 SCREEN 963 AND 970 AND 2067
L10 SCREEN 1821 OR 1822 OR 1823 OR 1824
L11 STRUCTURE UPLOADED
L12 QUE L11 AND L9 AND L10
L13 2 S L12 FULL
L14 SCREEN 970 AND 2067
L15 STRUCTURE UPLOADED
L16 QUE L15 AND L14
L17 4983 S L16 FULL
L18 SCREEN 963 AND 970 AND 2067
L19 STRUCTURE UPLOADED
L20 QUE L19 AND L18
L21 97 S L20 FULL
L22 SCREEN 2067
L23 STRUCTURE UPLOADED
L24 QUE L23 AND L22
L25 11293 S L24 FULL
L26 SCREEN 2067
L27 STRUCTURE UPLOADED
L28 QUE L27 AND L26
L29 850 S L28 FULL
L30 3 S L4 AND (L17 OR L21 OR L25 OR L29)
L31 3 S L8 AND (L17 OR L21 OR L25 OR L29)
L32 0 S L13 AND (L17 OR L21 OR L25 OR L29)
L33 0 S L31 NOT L30
L34 SCREEN 2067
L35 STRUCTURE UPLOADED
L36 QUE L35 AND L34
L37 7 S L36 FULL
L38 SCREEN 2067
L39 STRUCTURE UPLOADED
L40 QUE L39 AND L38
L41 0 S L40 FULL
L42 7 S L37 AND (L17 OR L21 OR L25 OR L29)

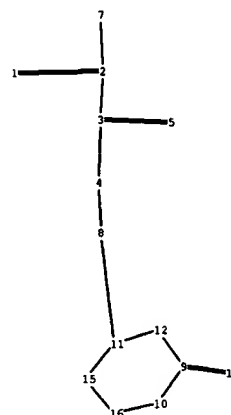
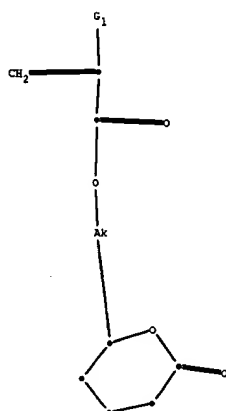
FILE 'CAPLUS' ENTERED AT 14:01:10 ON 11 SEP 2002

L43 1 S L30
L44 3 S L42

FILE 'REGISTRY' ENTERED AT 14:02:48 ON 11 SEP 2002

L45 SCREEN 970 AND 2067
L46 STRUCTURE UPLOADED
L47 QUE L46 AND L45
L48 0 S L47 FULL
L49 SCREEN 2067
L50 STRUCTURE UPLOADED
L51 QUE L50 AND L49
L52 0 S L51 FULL

=>



chain nodes :

1 2 3 4 5 7 8 13

ring nodes :

9 10 11 12 15 16

chain bonds :

1-2 2-3 2-7 3-4 3-5 4-8 8-11 9-13

ring bonds :

9-10 9-12 10-16 11-12 11-15 15-16

exact/norm bonds :

2-7 3-4 3-5 4-8 8-11 9-10 9-12 9-13 10-16 11-12 11-15 15-16

exact bonds :

1-2 2-3

G1:H,CH3

Match level :

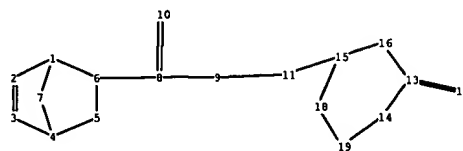
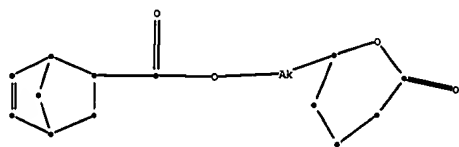
1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 7:CLASS 8:CLASS 9:Atom
10:Atom 11:Atom 12:Atom 13:CLASS 15:CLASS 16:Atom

Generic attributes :

8:
Saturation : Saturated

Element Count :

Node 8: Limited
C,C1-5



chain nodes :

8 9 10 11 17

ring nodes :

1 2 3 4 5 6 7 13 14 15 16 18 19

chain bonds :

6-8 8-9 8-10 9-11 11-15 13-17

ring bonds :

1-2 1-6 1-7 2-3 3-4 4-5 4-7 5-6 13-14 13-16 14-19 15-16 15-18
18-19

exact/norm bonds :

1-2 1-6 1-7 2-3 3-4 4-5 4-7 5-6 8-9 8-10 9-11 11-15 13-14
13-16 13-17 14-19 15-16 15-18 18-19

exact bonds :

6-8

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:Atom 8:CLASS 9:CLASS
10:CLASS 11:CLASS 13:Atom 14:Atom 15:Atom 16:Atom 17:CLASS 18:Atom
19:Atom

Element Count :

Node 11: Limited
C,C1-5

L43 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2002 ACS

AN 2001:900258 CAPLUS

DN 136:29177

TI Radiation-sensitive resin composition for chem. amplified pos. tone resist

IN Nishimura, Yukio; Douki, Katsuji; Kajita, Toru; Shimokawa, Tsutomu

PA JSR Corporation, Japan

SO Eur. Pat. Appl., 54 pp.

CODEN: EPXXDW

DT Patent

LA English

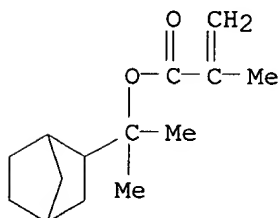
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1162506	A1	20011212	EP 2001-113944	20010607
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2002062657	A2	20020228	JP 2001-95877	20010329
	US 2002009667	A1	20020124	US 2001-874977	20010607
PRAI	JP 2000-173708	A	20000609		
	JP 2001-95877	A	20010329		
AB	A radiation-sensitive resin compn. used as a chem. amplified pos. tone resist responsive to short wavelength active radiation such as KrF excimer laser and ArF excimer laser is disclosed. The resin compn. comprises: (A) an acid-dissociable group-contg. resin which is insol. or scarcely sol. in alkali and becomes alkali sol. when the acid-dissociable group dissocs., the resin comprising a lactone cyclic structure I (a = 1-3; b = 0-9; R1 = monovalent org. group); and (B) a photoacid generator. The compn. has high transmittance of radiation, exhibits high sensitivity, resolu., and pattern shape, and can produce semiconductors at a high yield without producing resolu. defects during microfabrication.				
IT	379257-73-5P 379257-75-7P 379257-76-8P RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (radiation-sensitive resin compn. for chem. amplified pos. tone resist)				
RN	379257-73-5 CAPLUS				
CN	2-Propenoic acid, 2-methyl-, 1-bicyclo[2.2.1]hept-2-yl-1-methylethyl ester, polymer with (tetrahydro-5-oxo-2-furanyl)methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				

CM 1

CRN 342014-18-0

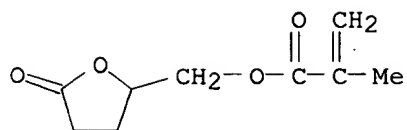
CMF C14 H22 O2



CM 2

CRN 156938-09-9

CMF C9 H12 O4



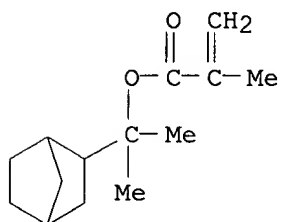
RN 379257-75-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-bicyclo[2.2.1]hept-2-yl-1-methylethyl ester, polymer with 3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl 2-methyl-2-propenoate and (tetrahydro-5-oxo-2-furanyl)methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 342014-18-0

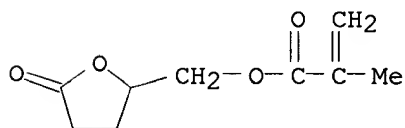
CMF C14 H22 O2



CM 2

CRN 156938-09-9

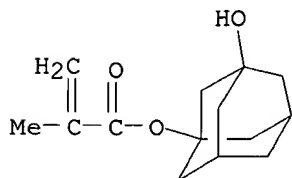
CMF C9 H12 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



RN 379257-76-8 CAPLUS

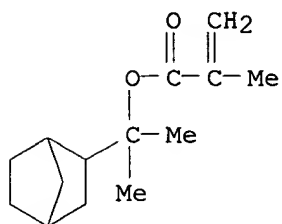
CN 2-Propenoic acid, 2-methyl-, 1-bicyclo[2.2.1]hept-2-yl-1-methylethyl ester, polymer with bicyclo[2.2.1]hept-2-ene, 2,5-furandione and 3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl 2-methyl-2-propenoate

(tetrahydro-5-oxo-2-furanyl)methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 342014-18-0

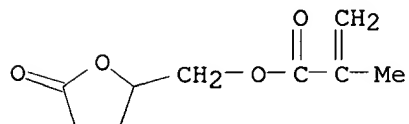
CMF C14 H22 O2



CM 2

CRN 156938-09-9

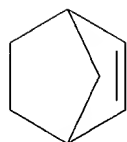
CMF C9 H12 O4



CM 3

CRN 498-66-8

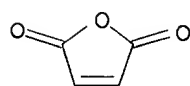
CMF C7 H10



CM 4

CRN 108-31-6

CMF C4 H2 O3



RE.CNT 4

THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L44 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2002 ACS

AN 2001:900258 CAPLUS

DN 136:29177

TI Radiation-sensitive resin composition for chem. amplified pos. tone resist

IN Nishimura, Yukio; Douki, Katsuji; Kajita, Toru; Shimokawa, Tsutomu

PA JSR Corporation, Japan

SO Eur. Pat. Appl., 54 pp.

CODEN: EPXXDW

DT Patent

LA English

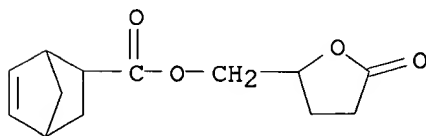
FAN.CNT 1

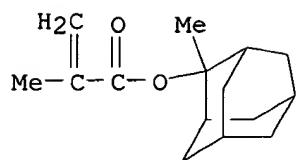
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1162506	A1	20011212	EP 2001-113944	20010607
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2002062657	A2	20020228	JP 2001-95877	20010329
	US 2002009667	A1	20020124	US 2001-874977	20010607
PRAI	JP 2000-173708	A	20000609		
	JP 2001-95877	A	20010329		
AB	A radiation-sensitive resin compn. used as a chem. amplified pos. tone resist responsive to short wavelength active radiation such as KrF excimer laser and ArF excimer laser is disclosed. The resin compn. comprises: (A) an acid-dissociable group-contg. resin which is insol. or scarcely sol. in alkali and becomes alkali sol. when the acid-dissociable group dissocs., the resin comprising a lactone cyclic structure I (a = 1-3; b = 0-9; R1 = monovalent org. group); and (B) a photoacid generator. The compn. has high transmittance of radiation, exhibits high sensitivity, resolu., and pattern shape, and can produce semiconductors at a high yield without producing resolu. defects during microfabrication.				
IT	379257-77-9P 379257-78-0P 379257-82-6P 379257-83-7P				
	RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				
	(radiation-sensitive resin compn. for chem. amplified pos. tone resist)				
RN	379257-77-9 CAPLUS				
CN	Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, (tetrahydro-5-oxo-2-furanyl)methyl ester, polymer with bicyclo[2.2.1]hept-2-ene, 2,5-furandione and 2-methyltricyclo[3.3.1.1 ^{3,7}]dec-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				

CM 1

CRN 264193-11-5

CMF C13 H16 O4

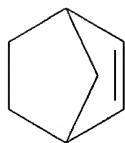




CM 3

CRN 498-66-8

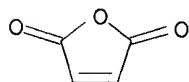
CMF C7 H10



CM 4

CRN 108-31-6

CMF C4 H2 O3



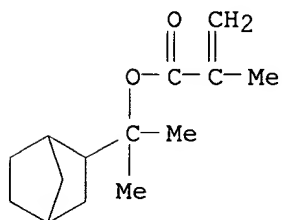
RN 379257-78-0 CAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, (tetrahydro-5-oxo-2-furanyl)methyl ester, polymer with bicyclo[2.2.1]hept-2-ene, 1-bicyclo[2.2.1]hept-2-yl-1-methylethyl 2-methyl-2-propenoate and 2,5-furandione (9CI) (CA INDEX NAME)

CM 1

CRN 342014-18-0

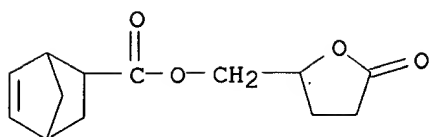
CMF C14 H22 O2



CM 2

CRN 264193-11-5

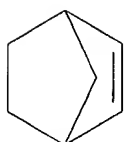
CMF C13 H16 O4



CM 3

CRN 498-66-8

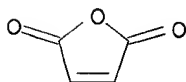
CMF C7 H10



CM 4

CRN 108-31-6

CMF C4 H2 O3



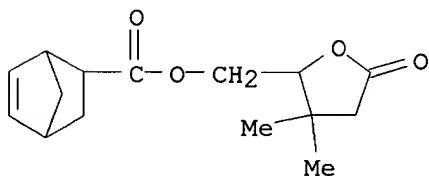
RN 379257-82-6 CAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione and (tetrahydro-3,3-dimethyl-5-oxo-2-furanyl)methyl bicyclo[2.2.1]hept-5-ene-2-carboxylate (9CI) (CA INDEX NAME)

CM 1

CRN 379257-70-2

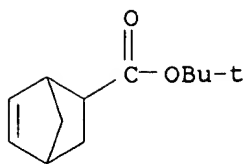
CMF C15 H20 O4



CM 2

CRN 154970-45-3

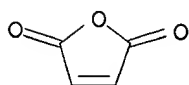
CMF C12 H18 O2



CM 3

CRN 108-31-6

CMF C4 H2 O3



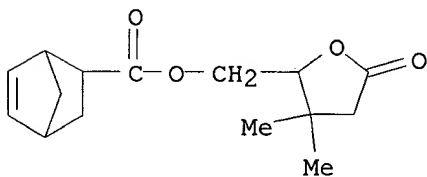
RN 379257-83-7 CAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and (tetrahydro-3,3-dimethyl-5-oxo-2-furanyl)methyl bicyclo[2.2.1]hept-5-ene-2-carboxylate (9CI) (CA INDEX NAME)

CM 1

CRN 379257-70-2

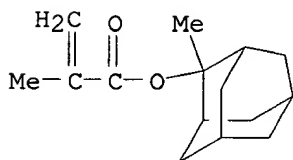
CMF C15 H20 O4



CM 2

CRN 177080-67-0

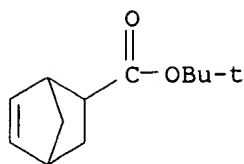
CMF C15 H22 O2



CM 3

CRN 154970-45-3

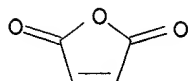
CMF C12 H18 O2



CM 4

CRN 108-31-6

CMF C4 H2 O3



RE.CNT 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L44 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2002 ACS

AN 2000:249842 CAPLUS

DN 132:300943

TI Hydrogenated polymer prepared by metathesis ring-opening polymerization and the use and manufacture of the polymer

IN Sunaga, Tadahiho; Takao, Toshiro; Ikeda, Keiichi; Yamamoto, Yoshihiro; Kawahara, Nobuo; Okita, Masumizu

PA Mitsui Chemicals Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 42 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000109545	A2	20000418	JP 1999-183991	19990629
	US 6372854	B1	20020416	US 1999-339538	19990624
	TW 445269	B	20010711	TW 1999-88110832	19990628
	KR 2000006560	A	20000125	KR 1999-25544	19990629
PRAI	JP 1998-182916	A	19980629		
	JP 1998-221756	A	19980805		

AB The hydrogenated polymer involves repeating unit I (R1-R4 are alkyl, halogen, etc., including acid-decomposable group; X1 = O, S, NR, PR, CR; R = alkyl), I (R1-R4 are alkyl, halogen, etc., without acid-decomposable group), and optionally I (.gtoreq.1 of R1-R4 is cyano- or lactonyloxycarbonyl-contg. group) and the mol. wt. distribution of the polymer is narrow. The polymer is manufd. by ring-opening living polymn. using metathesis catalysts. The polymer is used as a photoresist, which shows improved adhesion to substrate and suitable for UV or far-UV photolithog. in semiconductor device fabrication.

IT **264193-12-6DP**, hydrogenated

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(ring-opening living polymn. using metathesis catalyst followed by hydrogenation for polymer for photoresist)

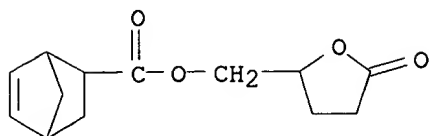
RN 264193-12-6 CAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, (tetrahydro-5-oxo-2-furanyl)methyl ester, polymer with bicyclo[2.2.1]hept-5-ene-2-carbonitrile (9CI) (CA INDEX NAME)

CM 1

CRN 264193-11-5

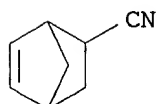
CMF C13 H16 O4



CM 2

CRN 95-11-4

CMF C8 H9 N



L44 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2002 ACS

AN 1995:1003165 CAPLUS

DN 124:118191

TI Preparation of "Sugar-Coated" Homopolymers and Multiblock ROMP Copolymers

AU Nomura, Kotohiro; Schrock, Richard R.

CS Department of Chemistry, Massachusetts Institute of Technology, Cambridge, MA, 02139, USA

SO Macromolecules (1996), 29(2), 540-5

CODEN: MAMOBX; ISSN: 0024-9297

PB American Chemical Society

DT Journal

LA English

AB Ring-opened homopolymers of 5-norbornene-2-carboxylates or 5-norbornene-2,3-dicarboxylates that contain acetal-protected sugars 1,2:3,4-di-O-isopropylidene-.alpha.-D-galactopyranos-6-O-yl 5-norbornene-2-carboxylate (I), bis(1,2:3,4-di-O-isopropylidene-.alpha.-D-galactopyranos-6-O-yl) 5-norbornene-trans-2,3-dicarboxylate (II), 5-norbornene-2-carboxylic acid ester contg. 2,3-O-isopropylidene-D-ribonic .gamma.-lactone, or 3,4:5,6-di-O-isopropylidene-.alpha.-D-mannofuranos-1-O-yl 5-norbornene-2-carboxylate were prepd. in toluene using Mo(CHCMe2Ph)(N-2,6-i-Pr2C6H3)(O-t-Bu)2 as the initiator. These homopolymers showed narrow mol. wt. distributions (PDI = 1.02-1.25) and a mol. wt. dependent on the no. of monomers added. Di-, tri-, and tetrablock copolymers contg. 1-4, methyltetracyclododecene or trans-2,3-bis(((trimethylsilyl)oxy)methyl)-norborn-5-ene were also prepd. and found to have low polydispersities (Mw/Mn = 1.03-1.25). The cyclic acetal in polymers contg. I or II could be removed using CF3CO2H/H2O (9/1 vol./vol., 15 min, 22.degree.) to afford the corresponding water-sol. polymers contg. the parent sugar.

IT 172954-93-7P 172955-00-9P

RL: SPN (Synthetic preparation); PREP (Preparation)

(prepn. of sugar-contg. homopolymers and multiblock ROMP copolymers)

RN 172954-93-7 CAPLUS

CN D-Ribonic acid, 2,3-O-(1-methylethylidene)-, .gamma.-lactone,

5-bicyclo[2.2.1]hept-5-ene-2-carboxylate, homopolymer (9CI) (CA INDEX NAME)

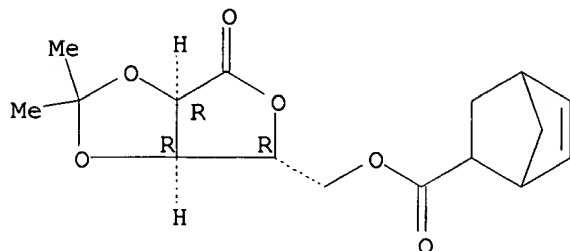
CM 1

CRN 172954-92-6

CMF C16 H20 O6

CDES 5:D-RIBO

Absolute stereochemistry.



RN 172955-00-9 CAPLUS

CN D-Ribonic acid, 2,3-O-(1-methylethylidene)-, .gamma.-lactone, 5-bicyclo[2.2.1]hept-5-ene-2-carboxylate, polymer with 1,2:3,4-bis-O-(1-methylethylidene)-.alpha.-D-galactopyranose bicyclo[2.2.1]hept-5-ene-2-carboxylate, block (9CI) (CA INDEX NAME)

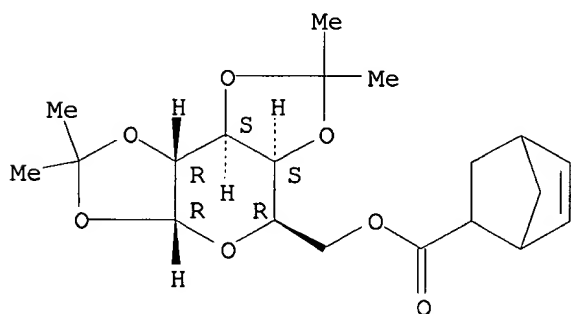
CM 1

CRN 172954-94-8

CMF C20 H28 O7

CDES 5:A-D-GALACTO

Absolute stereochemistry.



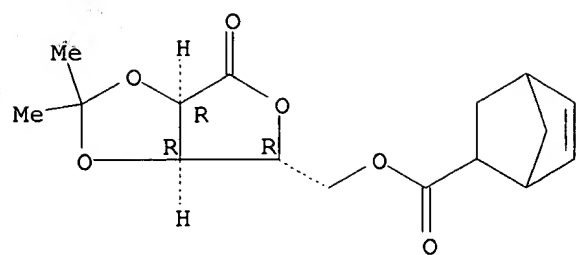
CM 2

CRN 172954-92-6

CMF C16 H20 O6

CDES 5:D-RIBO

Absolute stereochemistry.



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